

Application No. 09/449,907  
Attorney Docket No. 107176-09004

the workpiece for polishing the same and disposed in a first plane;  
polishing agent passages, having bottoms disposed in a second plane, for  
introducing a polishing agent; and

*B1*  
*CONC* a plurality of one-stage step portions formed between said polishing faces of said  
polishing projections and the bottoms of said polishing agent passages and disposed in  
a third plane, the first, second and third planes spaced apart from and extending  
parallel to one another.

*54.* (Once Amended) A chemical mechanical polishing apparatus,  
comprising:  
a chemical mechanical polishing cloth for chemically mechanically polishing a  
workpiece;

a polishing head for holding and rubbing a workpiece with said chemical  
mechanical polishing cloth; and

a polishing agent supply mechanism for supplying a polishing agent to said  
chemical mechanical polishing cloth,

*B2*  
said chemical mechanical polishing cloth including, on an opposite-to-  
workpiece face thereof:

polishing projections having polishing faces arranged to come in contact with  
the workpiece for polishing the same and disposed in a first plane;

polishing agent passages, having bottoms disposed in a second plane, for  
introducing a polishing agent; and

a plurality of one-stage step portions formed between said polishing faces of  
said polishing projections and the bottoms of said polishing agent passages and